JC05 Rec'd PCT/PTO

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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

SAC

In re application of

Attn: BOX PCT

Akihisa HONGO of al.

Serial No. NEW 09/7

Docket No. 2001_013/3A

Filed February 9, 2001

SUBSTRATE PLATING METHOD AND APPARATUS [Corresponding to PCT/JP99/04349 Filed August 11, 1999]

THE COMMISSIONER IS AUTHORIZED TO CHARGE ANY DEFICIENCY IN THE FEE FOR THIS PAPER TO DEPOSIT ACCOUNT NO. 23-0975.

PRELIMINARY AMENDMENT

Assistant Commissioner for Patents Washington, DC 20231

Sir:

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Prior to initial examination of the above-identified application, kindly amend the application as follows:

IN THE CLAIMS:

Kindly amend claims 3, 5-6, 8 and 11 as follows:

A

A method or apparatus for plating a substrate according to claim 1, comprising in said electroless plating process or said electroless plating bath:

means for disposing a substrate to be plated in such a state that a surface to be processed thereof faces upwardly, and forming a hermetically sealed space by said surface to be processed; and